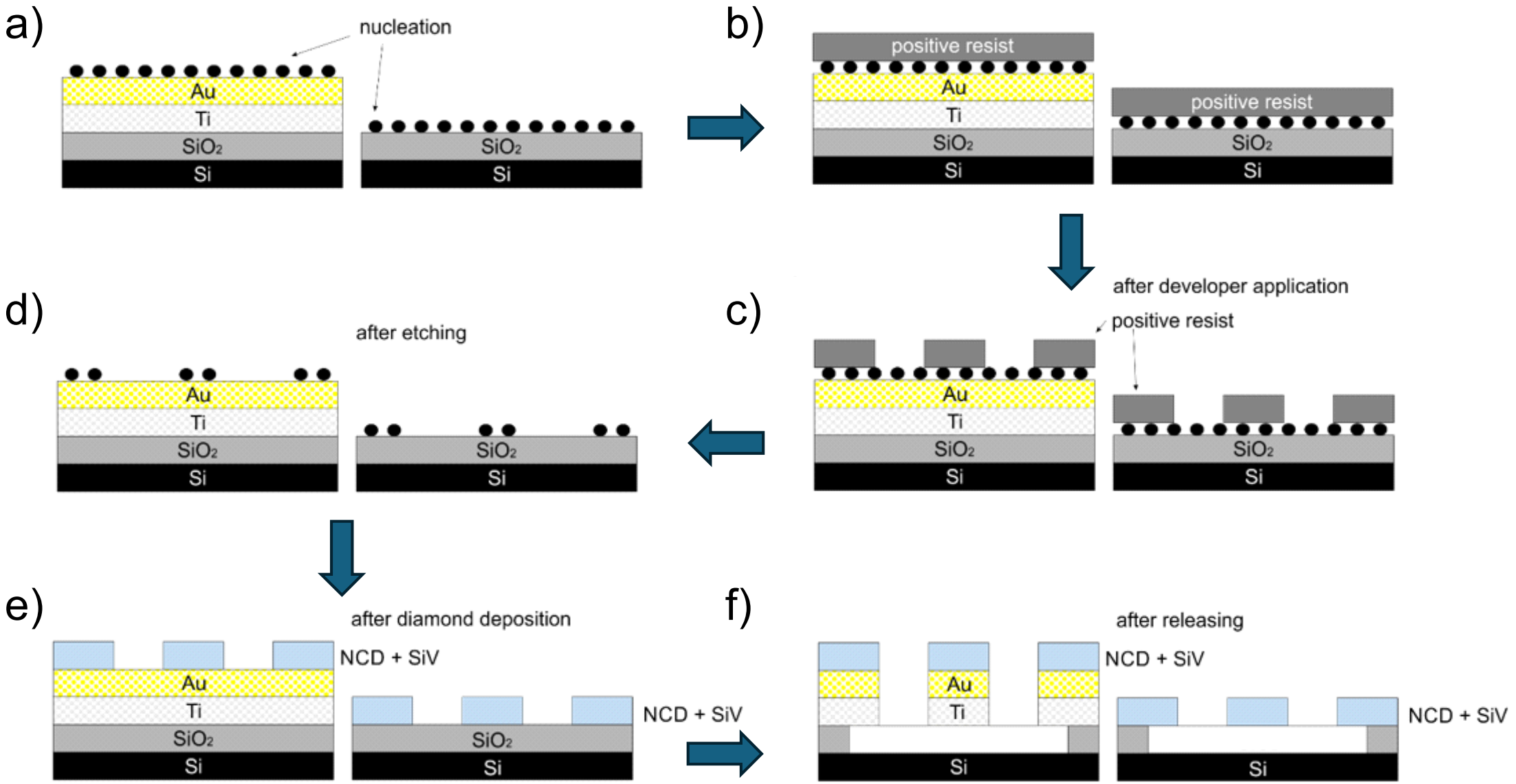
a)
nucleation
Au
Ti
SiO2
Si
SiO2
Si
b)
positive resist
Au
Ti
SiO2
Si
positive resist
SiO2
Si
after developer application
c)
positive resist
Au
Ti
SiO2
Si
SiO2
Si
d)
after etching
Au
Ti
SiO2
Si
SiO2
Si
e)
after diamond deposition
NCD + SiV
Au
Ti
SiO2
Si
SiO2
Si
NCD + SiV
f)
after releasing
NCD + SiV
Au
Ti
Si
Si
NCD + SiV